

**Amendments to the Claims**

Claims 1-10 (Cancelled).

11. (Previously presented): A boron and/or phosphorus doped silicon dioxide selective to undoped  $\text{SiO}_2$  and  $\text{Si}_3\text{N}_4$  etchant gas composition, consisting essentially of:

- a carrier gas;
- at least one of  $\text{C}_4\text{F}_6$  and  $\text{C}_5\text{F}_8$ ;
- $\text{CH}_2\text{F}_2$ ; and
- $\text{CF}_4$ , the etchant gas composition being selective to both undoped  $\text{SiO}_2$  and  $\text{Si}_3\text{N}_4$  relative to doped  $\text{SiO}_2$  comprising one or both of boron and phosphorous.

Claims 12 and 13 (Cancelled).

14. (Original): The etchant gas composition according to Claim 11, wherein the carrier gas is selected from the group consisting of argon, helium, and xenon.

15. (Previously Presented): The etchant gas composition according to Claim 11, wherein the carrier gas comprises argon.

16. (Previously presented): A boron and/or phosphorus doped silicon dioxide selective to undoped  $\text{SiO}_2$  and  $\text{Si}_3\text{N}_4$  etchant gas composition, consisting essentially of:

a carrier gas;

at least one of  $\text{C}_4\text{F}_6$  and  $\text{C}_5\text{F}_8$ ;

$\text{CH}_2\text{F}_2$ ;

$\text{CHF}_3$ ; and

$\text{CF}_4$  constituting a boron and/or phosphorus doped silicon dioxide selective to undoped  $\text{SiO}_2$  and  $\text{Si}_3\text{N}_4$  etchant gas composition.

Claims 17 and 18 (Cancelled).

19. (Previously presented): The etchant gas composition according to Claim 16, wherein the carrier gas is selected from the group consisting of argon, helium, and xenon.

20. (Previously Presented): The etchant gas composition according to Claim 16, wherein the carrier gas comprises argon.

Claims 21-68. (Cancelled).

69. (Previously Presented): The etchant gas composition according to Claim 11 wherein the carrier gas comprises helium.

70. (Previously Presented): The etchant gas composition according to Claim 16 wherein the carrier gas comprises helium.

Claims 71- 72 (Cancelled).

73. (Previously Presented): The etchant gas composition according to Claim 11 wherein the carrier gas comprises xenon.

74. (Previously Presented): The etchant gas composition according to Claim 16 wherein the carrier gas comprises xenon.

Claims 75-80 (Cancelled).

81. (Currently amended): The etchant gas composition according to Claim 11, containing ~~contains~~  $C_4F_6$ .

Claim 82 (Cancelled).

83. (Currently amended): The etchant gas composition according to Claim 11, containing ~~contains~~  $C_5F_8$ .

84. (Currently amended): The etchant gas composition according to Claim 16, containing ~~contains~~  $C_4F_6$ .

Claim 85 (Cancelled).

86. (Currently amended): The etchant gas composition according to Claim 16, containing ~~contains~~  $C_5F_8$ .